

Title (en)  
PROCESS FOR FABRICATING NANOLITHOGRAPHY MASKS

Title (de)  
VERFAHREN ZUR HERSTELLUNG VON NANOLITHOGRAFIEMASKEN

Title (fr)  
PROCEDE DE FABRICATION DE MASQUE DE NANOLITHOGRAPHIE

Publication  
**EP 2936249 A1 20151028 (FR)**

Application  
**EP 13818313 A 20131216**

Priority

- FR 1262610 A 20121221
- FR 2013053102 W 20131216

Abstract (en)  
[origin: WO2014096662A1] The invention relates to a process for fabricating nanolithography masks from a film (20) of PS-b-PMMA block copolymer deposited on a surface (10) to be etched, said copolymer film comprising PMMA nanodomains (21) oriented perpendicularly to the surface to be etched, said process being characterised in that it comprises the following steps: irradiating (E1) part of said copolymer film in order to form a first irradiated zone and a second non-irradiated zone in said copolymer film, then treating (E2) said copolymer film in a developer solvent in order to remove, selectively, at least said PMMA nanodomains of said first irradiated zone of said copolymer film.

IPC 8 full level  
**G03F 7/32** (2006.01); **C08L 53/00** (2006.01); **G03F 7/00** (2006.01)

CPC (source: EP US)  
**B82Y 30/00** (2013.01 - US); **C08L 53/00** (2013.01 - EP US); **G03F 1/00** (2013.01 - US); **G03F 1/76** (2013.01 - US); **G03F 7/0002** (2013.01 - EP US); **G03F 7/325** (2013.01 - EP US); **H01L 21/0274** (2013.01 - US)

Citation (search report)  
See references of WO 2014096662A1

Designated contracting state (EPC)  
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)  
BA ME

DOCDB simple family (publication)  
**FR 3000235 A1 20140627**; **FR 3000235 B1 20160624**; CN 104885013 A 20150902; CN 104885013 B 20190625; EP 2936249 A1 20151028; JP 2016516288 A 20160602; JP 2018117132 A 20180726; JP 6324991 B2 20180516; KR 101709028 B1 20170221; KR 20150088799 A 20150803; SG 11201504292Q A 20150730; TW 201441292 A 20141101; TW I557172 B 20161111; US 2015331313 A1 20151119; US 9599890 B2 20170321; WO 2014096662 A1 20140626

DOCDB simple family (application)  
**FR 1262610 A 20121221**; CN 201380067287 A 20131216; EP 13818313 A 20131216; FR 2013053102 W 20131216; JP 2015548711 A 20131216; JP 2018024900 A 20180215; KR 20157013562 A 20131216; SG 11201504292Q A 20131216; TW 102146664 A 20131217; US 201314654277 A 20131216